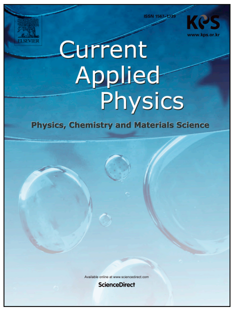

Effects of deposition parameters on the structure and mechanical properties of high-entropy alloy nitride films

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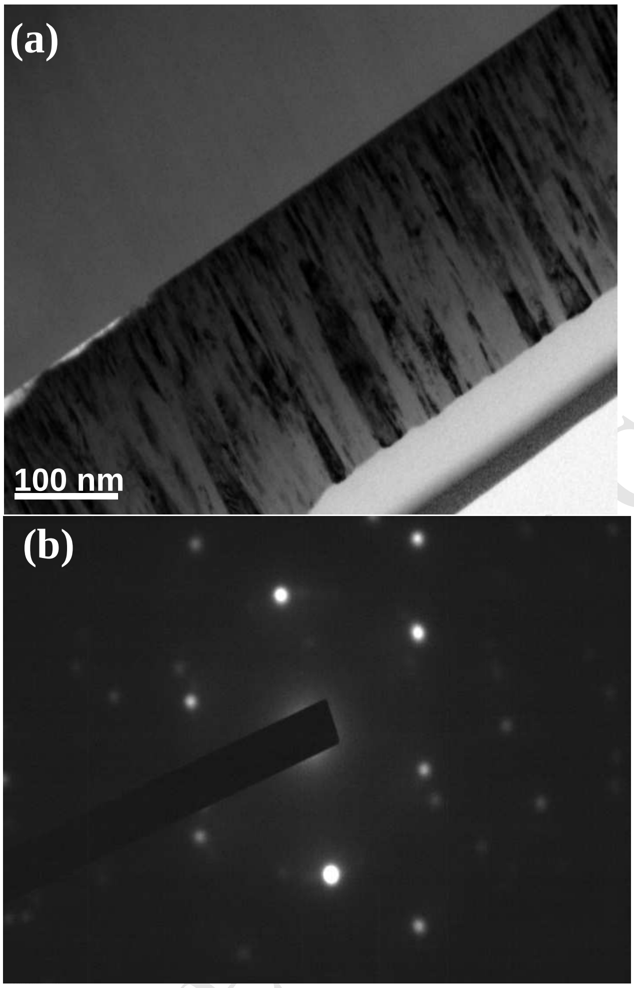
Graphical Abstract



Bright-field plan view TEM images and their corresponding SAD patterns for the (AlCrNbSiTiV)N film coatings, show that there is a simple FCC crystal phase.